Notice of References Cited	Application/Control No. 10/683,534	Applicant(s)/Patent Under Reexamination MELVIN, LAWRENCE S.	
	Examiner Andre Pierre-Louis	Art Unit 2123	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,792,591	09-2004	Shi et al.	716/19
	B	US-			
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Melvin III et al. (Model-based methodology for reducing OPC output pattern complexity, SPIE 2003).
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.